

L Number	Hits	Search Text	DB	Time stamp
42	0	suspension near (water near soluble) near (oxide silica ((germanium silicon) adj dioxide)) near particle	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 13:55
43	606	suspension same (water near soluble) same (oxide silica ((germanium silicon) adj dioxide)) same particle	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 14:59
44	29	(suspension same (water near soluble) same (oxide silica ((germanium silicon) adj dioxide)) same particle) same (surface near (treated modified treating modifying treat modify coat coated coating))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 13:55
45	1	((suspension same (water near soluble) same (oxide silica ((germanium silicon) adj dioxide)) same particle) same (surface near (treated modified treating modifying treat modify coat coated coating))) and ((dielectric insulating) same binder)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 11:20
46	26030	428/447,116,304.4,308.4,312.2,312.6,315.7,318.4,319.1,319.3,332,450,209,148,427/387,189,108,189,201,236,243,2	US-PGPUB; EPO; JPO; DERWENT	
47	71661	(particle powder) same (void pore)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 12:16
48	3825	((particle powder) same (void pore)) same (nanometer nanometere nm!)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 14:01
49	106	((dielectric insulating) near film) and (((particle powder) same (void pore)) same (nanometer nanometere nm!))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 14:39
50	2	((dielectric insulating) near film) and ((pore porous void) near (monodisperse monodispersed monodispersion monodispersion))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 12:18
51	58	((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and lattice	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 12:18
52	55	((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and (silsesquioxane polyorganosilsesquioxane organosilsesquioxane organopolysilsesquioxane polysilsesquioxane methylsilsesquioxane hydrogensilsesquioxane phenylsilsesquioxane polyhydrogensilsesquioxane hydrogenpolysilsesquioxane polymethylsilsesquioxane methylpolysilsesquioxane polyphenylsilsesquioxane phenylpolysilsesquioxane)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 12:18

53	74	((dielectric insulating) near film) and (((particle powder) same (void pore)) same (nanometer nanometere nm!))) not (((suspension same (water near soluble) same (oxide silica ((germanium silicon) adj dioxide)) same particle) same (surface near (treated modified treating modifying treat modify coat coated coating))) and ((dielectric insulating) same binder)) (((dielectric insulating) near film) and ((pore porous void) near (monodisperse monodispersed monodispersion monodispersion)))) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and lattice) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and (silsesquioxane polyorganosilsesquioxane organosilsesquioxane organopolysilsesquioxane polysilsesquioxane methylsilsesquioxane hydrogensilsesquioxane phenylsilsesquioxane polyhydrogensilsesquioxane hydrogenpolysilsesquioxane polymethylsilsesquioxane methylpolysilsesquioxane polyphenylsilsesquioxane phenylpolysilsesquioxane))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 12:25
54	45	((particle powder) same (void pore)) same (nanometer nanometere nm!)) same ((uniform uniformly equal equally) near (space spaced separated distribute distributed distributing separate dispersed disperse))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 12:23
56	0	((dielectric insulating) near (binder film)) and (((particle powder) same (void pore)) same (nanometer nanometere nm!)) same ((uniform uniformly equal equally) near (space spaced separated distribute distributed distributing separate dispersed disperse))) not (((suspension same (water near soluble) same (oxide silica ((germanium silicon) adj dioxide)) same particle) same (surface near (treated modified treating modifying treat modify coat coated coating))) and ((dielectric insulating) same binder)) (((dielectric insulating) near film) and ((particle powder) same (void pore)) same (nanometer nanometere nm!))) (((dielectric insulating) near film) and ((pore porous void) near (monodisperse monodispersed monodispersion monodispersion)))) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and lattice) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and (silsesquioxane polyorganosilsesquioxane organosilsesquioxane organopolysilsesquioxane polysilsesquioxane methylsilsesquioxane hydrogensilsesquioxane phenylsilsesquioxane polyhydrogensilsesquioxane hydrogenpolysilsesquioxane polymethylsilsesquioxane methylpolysilsesquioxane polyphenylsilsesquioxane phenylpolysilsesquioxane))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 14:02
55	14	((dielectric insulating) near (binder film)) and (((particle powder) same (void pore)) same (nanometer nanometere nm!)) same ((uniform uniformly equal equally) near (space spaced separated distribute distributed distributing separate dispersed disperse)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 12:25

57	1	<p>(((dielectric insulating) near (binder film)) and (((particle powder) same (void pore)) same (nanometer nanometere nm!)) same ((uniform uniformly equal equally) near (space spaced separated distribute distributed distributing separate dispersed disperse))) not (((suspension same (water near soluble) same (oxide silica ((germanium silicon) adj dioxide)) same particle) same (surface near (treated modified treating modifying treat modify coat coated coating))) and ((dielectric insulating) same binder)) (((dielectric insulating) near film) and ((pore porous void) near (monodisperse monodispersed monodispersion monodispersion))) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and lattice) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and (silsesquioxane polyorganosilsesquioxane organosilsesquioxane organopolysilsesquioxane polysilsesquioxane methylsilsesquioxane hydrogensilsesquioxane phenylsilsesquioxane polyhydrogensilsesquioxane hydrogenpolysilsesquioxane polymethylsilsesquioxane methylpolysilsesquioxane polyphenylsilsesquioxane phenylpolysilsesquioxane))</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 12:26
58	73	<p>(((dielectric insulating) near film) and (((particle powder) same (void pore)) same (nanometer nanometere nm!))) not (((suspension same (water near soluble) same (oxide silica ((germanium silicon) adj dioxide)) same particle) same (surface near (treated modified treating modifying treat modify coat coated coating))) and ((dielectric insulating) same binder)) (((dielectric insulating) near film) and ((pore porous void) near (monodisperse monodispersed monodispersion monodispersion))) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and lattice) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and (silsesquioxane polyorganosilsesquioxane organosilsesquioxane organopolysilsesquioxane polysilsesquioxane methylsilsesquioxane hydrogensilsesquioxane phenylsilsesquioxane polyhydrogensilsesquioxane hydrogenpolysilsesquioxane polymethylsilsesquioxane methylpolysilsesquioxane polyphenylsilsesquioxane phenylpolysilsesquioxane))) not (((dielectric insulating) near (binder film)) and (((particle powder) same (void pore)) same (nanometer nanometere nm!)) same ((uniform uniformly equal equally) near (space spaced separated distribute distributed distributing separate dispersed disperse))) not (((suspension same (water near soluble) same (oxide silica ((germanium silicon) adj dioxide)) same particle) same (surface near (treated modified treating modifying treat modify coat coated coating))) and ((dielectric insulating) same binder)) (((dielectric insulating) near film) and ((pore porous void) near (monodisperse monodispersed monodispersion monodispersion))) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and (silsesquioxane polyorganosilsesquioxane organosilsesquioxane organopolysilsesquioxane polysilsesquioxane methylsilsesquioxane hydrogensilsesquioxane phenylsilsesquioxane polyhydrogensilsesquioxane hydrogenpolysilsesquioxane polymethylsilsesquioxane methylpolysilsesquioxane polyphenylsilsesquioxane phenylpolysilsesquioxane)))</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 12:26
59	804	<p>("3-D" 3d "three-dimensional" "3-dimensional" (three near dimesnional)) near lattice</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 13:56

60	16	((particle powder) same (void pore)) same (nanometer nanometere nm!) and (("3-D" 3d "three-dimensional" "3-dimensional" (three near dimesnional)) near lattice)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 14:01
61	15	(((particle powder) same (void pore)) same (nanometer nanometere nm!)) and (("3-D" 3d "three-dimensional" "3-dimensional" (three near dimesnional)) near lattice)) not (((suspension same (water near soluble) same (oxide silica ((germanium silicon) adj dioxide)) same particle) same (surface near (treated modified treating modifying treat modify coat coated coating))) and ((dielectric insulating) same binder)) (((dielectric insulating) near film) and (((particle powder) same (void pore)) same (nanometer nanometere nm!))) (((dielectric insulating) near film) and ((pore porous void) near (monodisperse monodispersed monodispersion monodispersion))) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and lattice) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and (silsesquioxane polyorganosilsesquioxane organosilsesquioxane organopolysilsesquioxane polysilsesquioxane methylsilsesquioxane hydrogensilsesquioxane phenylsilsesquioxane polyhydrogensilsesquioxane hydrogenpolysilsesquioxane polymethylsilsesquioxane methylpolysilsesquioxane polyphenylsilsesquioxane phenylpolysilsesquioxane) (((dielectric insulating) near film) and (((particle powder) same (void pore)) same (nanometer nanometere nm!))) not (((suspension same (water near soluble) same (oxide silica ((germanium silicon) adj dioxide)) same particle) same (surface near (treated modified treating modifying treat modify coat coated coating))) and ((dielectric insulating) same binder)) (((dielectric insulating) near film) and ((pore porous void) near (monodisperse monodispersed monodispersion monodispersion))) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and lattice) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and (silsesquioxane polyorganosilsesquioxane organosilsesquioxane organopolysilsesquioxane polysilsesquioxane methylsilsesquioxane hydrogensilsesquioxane phenylsilsesquioxane polyhydrogensilsesquioxane hydrogenpolysilsesquioxane polymethylsilsesquioxane methylpolysilsesquioxane polyphenylsilsesquioxane phenylpolysilsesquioxane))) (((dielectric insulating) near film) and (("3-D" 3d "three-dimensional" "3-dimensional" (three near dimesnional)) near lattice))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 14:13
62	9	428/447,116,304.4,308.4,312.2,312.6,315.7,318.4,319.1,319.3,332,450,209,148,27/387,189,198,199,204,236	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 14:13
63	16	and (("3-D" 3d "three-dimensional" "3-dimensional" (three near dimesnional)) near lattice)	US-PGPUB; EPO; JPO; DERWENT	243,2

71	219	<p>((dielectric insulating) near film) and ((curing cured cure crosslink crosslinking crosslinked harden hardening hardened vulcanize vulcanizing vulcanized) same (oven furnace) same (inert n?sub.2 he! Ar! nitrogen helium argon)) not (((suspension same (water near soluble) same (oxide silica ((germanium silicon) adj dioxide)) same particle) same (surface near (treated modified treating modifying treat modify coat coated coating))) and ((dielectric insulating) same binder)) (((dielectric insulating) near film) and ((particle powder) same (void pore)) same (nanometer nanometere nm!))) (((dielectric insulating) near film) and ((pore porous void) near (monodisperse monodispersed monodispersion monodispersion)))) (((((dielectric insulating) near film) and (pore porous void) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and lattice) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and (silsesquioxane polyorganosilsesquioxane organosilsesquioxane organopolysilsesquioxane polysilsesquioxane methylsilsesquioxane hydrogenpolysilsesquioxane phenylsilsesquioxane polyhydrogensilsesquioxane hydrogenpolysilsesquioxane polymethylsilsesquioxane methylpolysilsesquioxane polyphenylsilsesquioxane phenylpolysilsesquioxane) (((((dielectric insulating) near film) and ((particle powder) same (void pore)) same (nanometer nanometere nm!))) not (((suspension same (water near soluble) same (oxide silica ((germanium silicon) adj dioxide)) same particle) same (surface near (treated modified treating modifying treat </p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 15:02
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72	21	<p>428/447,116,304.4,308.4,312.2,312.6,315.7,318.4,319.1,319.3,332,450,209,148, A27/387, 1890, 080, 092, 204, 386, 243, 2</p> <p>and (((dielectric insulating) near film) and ((curing cured cure crosslink crosslinking crosslinked harden hardening hardened vulcanize vulcanizing vulcanized) same (oven furnace) same (inert n?sub.2 he! Ar! nitrogen helium argon))) not (((suspension same (water near soluble) same (oxide silica ((germanium silicon) adj dioxide)) same particle) same (surface near (treated modified treating modifying treat modify coat coated coating))) and ((dielectric insulating) same binder)) (((dielectric insulating) near film) and (((particle powder) same (void pore)) same (nanometer nanometere nm!))) (((dielectric insulating) near film) and ((pore porous void) near (monodisperse monodispersed monodispersion monodispersion)))) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and lattice) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and (silsesquioxane polyorganosilsesquioxane organosilsesquioxane organopolysilsesquioxane polysilsesquioxane methylsilsesquioxane hydrogensilsesquioxane phenylsilsesquioxane polyhydrogensilsesquioxane hydrogenpolysilsesquioxane polymethylsilsesquioxane methylpolysilsesquioxane polyphenylsilsesquioxane phenylpolysilsesquioxane) (((dielectric insulating) near film) and (((particle powder) same (void pore)) same (nanometer nanometere nm!))) not (((suspension same (water near soluble) same (oxide silica ((germanium silicon) adj dioxide)) same</p>
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Search History 8/20/03 3:41:16 PM Name: aged silica ((germanium silicon) adj dioxide)) same C:\APPS\EAST\Workspaces\2018-15\same\spurface near (treated modified treating modifying treat d f c c ed c g d deec c g e b de

	227	((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle (particles same (nanometer nanometere nm!)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 12:10
	236	((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 12:16
	12	(((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and ((first second) near phase)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 15:24
	11	(((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and ((first second) near phase)) not (((dielectric insulating) near film) and ((pore porous void) near (monodisperse monodispersed monodispersion monodispersion)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 11:23
	58	(((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and lattice	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 12:18
	55	(((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and (silsesquioxane polyorganosilsesquioxane organosilsesquioxane organopolysilsesquioxane polysilsesquioxane methylsilsesquioxane hydrogensilsesquioxane phenylsilsesquioxane polyhydrogensilsesquioxane hydrogenpolysilsesquioxane polymethylsilsesquioxane methylpolysilsesquioxane polyphenylsilsesquioxane phenylpolysilsesquioxane)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 12:18
	56	(((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and lattice) not (((dielectric insulating) near film) and ((pore porous void) near (monodisperse monodispersed monodispersion monodispersion))) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and ((first second) near phase))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 15:29
	39	(((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and (silsesquioxane polyorganosilsesquioxane organosilsesquioxane organopolysilsesquioxane polysilsesquioxane methylsilsesquioxane hydrogensilsesquioxane phenylsilsesquioxane polyhydrogensilsesquioxane hydrogenpolysilsesquioxane polymethylsilsesquioxane methylpolysilsesquioxane polyphenylsilsesquioxane phenylpolysilsesquioxane)) not (((dielectric insulating) near film) and ((pore porous void) near (monodisperse monodispersed monodispersion monodispersion))) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and ((first second) near phase)) (((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm!)))) and lattice))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/20 12:18
	1	"6159842".PN.	USPAT	2003/08/20 07:08
	0	6566243.URPN.	USPAT	2003/08/20 07:09